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Atty Dkt No. ARC920010125US1
R&A No. 5075-0034
PATENT

Date

Signature

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:
Hiroshi ITO

Serial No.: 10/091,373

Filing Date: March 4, 2002

Title: COPOLYMER FOR USE IN CHEMICAL AMPLIFICATION RESISTS

Group Art Unit: 1752

Examiner: Unassigned

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
Washington, DC 20231

Sir:

This is an Information Disclosure Statement submitted for the Examiner's consideration. Applicants respectfully request that the Examiner review and make of record the references identified below.

A PTO-1449 form listing the references accompanies this paper. Applicants would appreciate the Examiner's initialing and returning the form to indicate that the references have been reviewed and made of record. The references are as follows:

U.S. PATENT DOCUMENTS		
Document No.	Issue Date or Publication Date	Name of Patentee or Applicant
5,344,742	9/6/94	Sinta et al.
6,087,064	7/11/00	Lin et al.

NONPATENT DOCUMENTS	
Chiba et al. (2000), "157 nm Resist Materials: A Progress Report," <i>Journal of Photopolymer Science and Technology</i> 13(4):657-664.	
Choi et al. (2000), "Design and Synthesis of New Photoresist Materials for ArF Lithography," <i>Advances in Resist Technology and Processing XVII, Proceeding of SPIE</i> 3999:54-61.	
Ito et al. (1981), "Methyl α -Trifluoromethylacrylate, an E-Beam and UV Resist," <i>IBM Technical Disclosure Bulletin</i> 24(2):991.	
Ito et al. (1982), "Polymerization of Methyl α -(Trifluoromethyl)acrylate and α -(Trifluoromethyl)Acrylonitrile and Copolymerization of These Monomers with Methyl Methacrylate," <i>Macromolecules</i> 15(3):915-920.	
Ito (1984), "Radical Reactivity and Q-e Values of Methyl α -(Trifluoromethyl)acrylate," <i>Macromolecules</i> 17(10):2204-2205.	
Ito et al. (1987), "Anionic Polymerization of α -(Trifluoromethyl)acrylate," <i>Recent Advances in Anionic Polymerization, Elsevier</i> , pp. 421-430.	

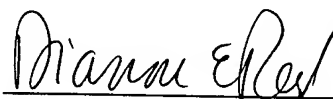
NONPATENT DOCUMENTS
Ito et al. (2001), "Novel Fluoropolymers for Use in 157 nm Lithography," <i>Journal of Photopolymer Science and Technology</i> 14(4):583-593.
Ito et al. (2001), "Polymer Design for 157 nm Chemically Amplified Resists," <i>Advances in Resist Technology and Processing XVIII, Proceedings of SPIE</i> 4345:273-284.
Kunz et al. (1999), "Outlook for 157 nm Resist Design," <i>Proceedings of SPIE</i> 3678:13-23.
Schmidt et al. (1962), "Ozonisierung Cyclischer Enolather," <i>Liebigs Ann. Chem. Bd.</i> 656:97-102.
Willson et al. (1983), "Poly(Methyl α -Trifluoromethylacrylate) as a Positive Electron Beam Resist," <i>Polymer Engineering and Science</i> 23(18):1000-1003.

This Information Disclosure Statement is not intended as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that any of the above references constitutes prior art to the present application within the meaning of 35 USC § 102.

As applicants have not yet received a first Action on the merits, no fee is required for filing this Information Disclosure Statement. If, however, the PTO finds that for some reason a fee is found to be necessary, our Deposit Account No. 18-0580 may be charged therefor. A duplicate copy of this paper is enclosed.

Respectfully submitted,

By:



Dianne E. Reed

Registration No. 31,292

REED & ASSOCIATES
800 Menlo Avenue, Suite 210
Menlo Park, California 94025
(650) 330-0900 Telephone
(650) 330-0980 Facsimile

Substitute for form 1449A/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

Sheet

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of

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Complete if Known

Application Number	10/091,373
Filing Date	March 4, 2002
First Named Inventor	Hiroshi ITO
Art Unit	1752
Examiner Name	Unassigned
Attorney Docket Number	ARC920010125US1

U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No.	Document No.	Issue Date or Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date if Appropriate
	AA	5,344,742	9/6/94	Sinta et al.			
	AB	6,087,064	7/11/00	Lin et al.			

OTHER DOCUMENTS — NONPATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), Title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T
	AC	Chiba et al. (2000), "157 nm Resist Materials: A Progress Report," <i>Journal of Photopolymer Science and Technology</i> 13(4):657-664.	
	AD	Choi et al. (2000), "Design and Synthesis of New Photoresist Materials for ArF Lithography," <i>Advances in Resist Technology and Processing XVII, Proceedings of SPIE</i> 3999:54-61.	
	AE	Ito et al. (1981), "Methyl α -Trifluoromethylacrylate, an E-Beam and UV Resist," <i>IBM Technical Disclosure Bulletin</i> 24(2):991.	
	AF	Ito et al. (1982), "Polymerization of Methyl α -(Trifluoromethyl)acrylate and α -(Trifluoromethyl)Acrylonitrile and Copolymerization of These Monomers with Methyl Methacrylate," <i>Macromolecules</i> 15(3):915-920.	
	AG	Ito (1984), "Radical Reactivity and Q-e Values of Methyl α -(Trifluoromethyl)acrylate," <i>Macromolecules</i> 17(10):2204-2205.	
	AH	Ito et al. (1987), "Anionic Polymerization of α -(Trifluoromethyl)acrylate," <i>Recent Advances in Anionic Polymerization, Elsevier</i> , pp. 421-430.	
	AI	Ito et al. (2001), "Novel Fluoropolymers for Use in 157 nm Lithography," <i>Journal of Photopolymer Science and Technology</i> 14(4):583-593.	
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	AL	Schmidt et al. (1962), "Ozonisierung Cyclischer Enolather," <i>Liebigs Ann. Chem. Bd.</i> 656:97-102.	
	AM	Willson et al. (1983), "Poly(Methyl α -Trifluoromethylacrylate) as a Positive Electron Beam Resist," <i>Polymer Engineering and Science</i> 23(18):1000-1003.	

Examiner
SignatureDate
Considered

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.